

Sheet 1 of 1

Subst. Form PTO-1449

Docket Number (Optional)

SAM-0483

Application Number

10/782,094

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

Applicant

Jae-eun Park, *et al.*

(Use several sheets if necessary)

Filing Date

02/19/04

Group Art Unit

2813

U. S. Patent Documents

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
TN	AA	6,090,442	07/18/00	Klaus, <i>et al.</i>	427	255.15	10/02/97
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
	AL							
	AM							
	AN							
	AO							
	AP							
	AQ							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	AR	
	AS	
	AT	

EXAMINER

T. N. N. N. N. N.

DATE CONSIDERED

12/16/05

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy with next communication to applicant.



Sheet 1 of 1

Subst. Form PTO-1449				Docket Number (Optional) SAM-0483		Application Number 10/782,094		
INFORMATION DISCLOSURE CITATION IN AN APPLICATION (Use several sheets if necessary)				Applicant Jae-eun Park, et al.				
				Filing Date 02/19/04		Group Art Unit 2813		
U. S. Patent Documents								
EXAMINER INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	AA			/				
TN	AB	5,470,800	11-28-95	Muroyama	437	238	03-26-93	
	AC	6,037,275	03-14-00	Wu, et al.	438	780	08-27-98	
	AD	6,270,572	08-07-01	Kim, et al.	117	93	08-09-99	
	AE	2002/0001974	01-03-02	Chan	438	785	06-20-01	
TN	AF	6,391,803	05-21-02	Kim, et al.	438	787	06-20-01	
	AG			/				
	AH			/				
	AI			/				
	AJ			/				
	AK			/				
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							YES	NO
TN	AL	06132276	05-13-94	Japan	H01L	21/312		X
	AM	1 096 042	05-02-01	Europe	C30B	25/02		
	AN	1 003 210	05-24-00	Europe	H01L	21/316		
	AO	10189582	07-21-98	Japan	H01L	21/316		X
	AP	2001002990	01-09-01	Japan	C09D	183/04		X
TN	AQ	1 139 399	10-04-01	Europe	H01L	21/306		
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
TN	AR	Klaus, J.W., et al., "Atomic layer controlled growth of SiO ₂ films using binary reaction sequence chemistry," American Institute of Physics, 1997, Pages 1092-1094						
	AS	/						
	AT	/						
EXAMINER T. NGUYEN					DATE CONSIDERED 12/16/05			
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy with next communication to applicant.								

1/3/05

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

Method of Forming Silicon Dioxide Using Siloxane

Application Number : 10/782094
 Confirmation Number: 4756
 First Named Applicant: Jae-Eun Park
 Attorney Docket Number: SAM-0483



Art Unit:

Examiner:

Search string: (6664156 or 5037514 or 6534395 or 20020164890 or 20030015764 or 20020047151).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
TN	1	6664156	2003-12-16	Ang, et al.		—	—
TN	2	5037514	1991-08-06	Yamazaki		—	—
TN	3	6534395	2003-03-18	Werkhoven, et al.		—	—

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
TN	1	20020164890	2002-11-17	Kwan, et al.		—	—
TN	2	20030015764	2003-01-23	Raaijmakers, et al.		—	—
TN	3	20020047151	2002-04-25	Kim, et al.		—	—

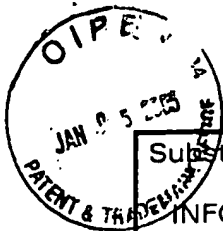
Remarks

Note: Remarks are not for responding to an office action.

part 1 of 1

Signature

Examiner Name	Date
T. NORTON	12/16/05



Sheet 1 of 1

Subst. Form PTO-1449

Docket Number (Optional)

SAM-0483

Application Number

10/782,094

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

Applicant

Jae-eun Park, et al.

Filing Date

02/19/04

Group Art Unit

2813

(Use several sheets if necessary)

U. S. Patent Documents

EXAMINER INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	BA						
	BB						
	BC						
	BD						
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	BI						
	BJ						
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FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
TN	BL	2002-0085487	11/16/02	Korea	H01L	21/20		X
	BM							
	BN							
	BO							
	BP							
	BQ							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	BR	
	BS	
	BT	

EXAMINER

T. Nguyen

DATE CONSIDERED

12/16/05


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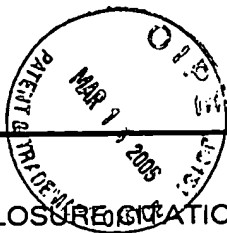
2/2/05

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

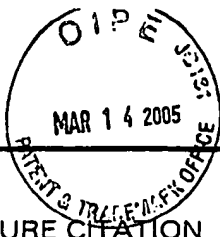
Stylesheet Version v18.0

Title of Invention	Method for forming silicon dioxide film using siloxane						
Application Number :		10/782094					
Confirmation Number:		4756					
First Named Applicant:		Jae-Eun Park					
Attorney Docket Number:		SAM-0483					
Art Unit:							
Examiner:							
Search string:		(20040096582).pn					
US Published Applications							
Note: Applicant is not required to submit a paper copy of cited US Published Applications							
init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
TM	1	20040096582	2004-05-20	Wang, et al.			
Remarks							
Note: Remarks are not for responding to an office action.							
Part 1 of 1.							
Signature							
Examiner Name				Date			
T. N. Nguyen				12/16/05			



Sheet 1 of 2

Subst. Form PTO-1449				Docket Number (Optional) SAM-0483		Application Number 10/782,094		
INFORMATION DISCLOSURE CITATION IN AN APPLICATION (Use several sheets if necessary)				Applicant Jae-eun Park, et al.				
				Filing Date 02/19/04		Group Art Unit 2813		
U. S. Patent Documents								
EXAMINER INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	AA							
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	AC							
	AD							
	AE							
	AF							
TN	AG	2002/0068466	06/06/02	Lee, et al.	438	765	05/31/01	
TN	AH	6,465,371	10/15/02	Lim	438	785	10/15/02	
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	AJ							
	AK							
FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation YES NO	
	AL							
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	AN							
	AO							
	AP							
	AQ							
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
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	AS							
	AT							
EXAMINER T. NGUYEN				DATE CONSIDERED 12/16/05				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy with next communication to applicant.								



Sheet 2 of 2

Subst. Form PTO-1449

Docket Number (Optional)

SAM-0483

Application Number

10/782,094

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

Applicant

Jae-eun Park, et al.

(Use several sheets if necessary)

Filing Date

02/19/04

Group Art Unit

2813

U. S. Patent Documents

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	BA						
	BB						
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	BK						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
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TN	BM	02-2579	01/10/02	Korea	H01L	21/316		X
TN	BN	02-44422	06/15/02	Korea	H01L	21/20		X
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	BP							
	BQ							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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	BS	
	BT	

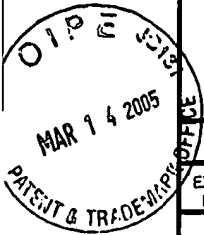
EXAMINER

T. NGUYEN

DATE CONSIDERED

12/16/05

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6/28/05

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

Method for forming silicon dioxide film using siloxane

Application Number : 10/782094
Confirmation Number: 4756
First Named Applicant: Jae-eun Park
Attorney Docket Number: SAM-0483
Art Unit:
Examiner:
Search string: (3313792).pn



US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
JM	1	3313792	1967-04-11	Duck, et al.			

Remarks

Note: Remarks are not for responding to an office action.

Part 1 of 1.

Signature

Examiner Name	Date
J. N. BROWN	12/16/05